AMENDMENT UNDER 37 C.F.R. § 1.114(c) Attorney Docket No.: Q96380

U.S. Application No.: 10/588,659

## AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

## LISTING OF CLAIMS:

1. (currently amended): A p-type semiconductor material expressed in a composition formula of  $Zn_{(1-\alpha,\beta,\gamma)}Cu_{\alpha}A_{\beta}B_{\gamma}S_{(1-x,\gamma)}Se_{\alpha}Te_{\gamma}$  (0.004  $\leq \alpha \leq$  0.4,  $\beta \leq$  0.2,  $\gamma \leq$  0.2, 0  $\leq x \leq 1$ ,  $0 \leq y \leq$  0.2, and  $x+y \leq 1$ , A and B are elements selected from Cd, Hg and alkaline earth metals),

wherein a total amount of atoms (Zn, Cu, A, B) is equal to a total amount of atoms (S, Se, Te)).

- (original): The p-type semiconductor material according to claim 1, wherein the A is Mg.
- (original): The p-type semiconductor material according to claim 1, wherein the B is Cd.
- (original): The p-type semiconductor material according to claim 2, wherein the B is Cd.
- 5. (previously presented): The p-type semiconductor material according to claim 1, wherein the semiconductor material contains at least one dopant selected from Cl, Br, I, Al, Ga and In as a compensation dopant and a concentration of the compensation dopant is 10<sup>17</sup> to 10<sup>20</sup> cm<sup>3</sup>.

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- 6. (previously presented): The p-type semiconductor material according to claim 1, wherein the semiconductor material has a light absorption coefficient of  $5 \times 10^5 \text{ cm}^{-1}$  or less at 470 nm to 750 nm.
- 7. (previously presented): The p-type semiconductor material according to claim 1, wherein a volume resistivity of the semiconductor material is equal to or higher than  $10^{4}\Omega$ cm and is lower than  $10^{3}\Omega$ cm.
- 8. (previously presented): The p-type semiconductor material according to claim 1, wherein a carrier concentration of the semiconductor material is equal to or higher than 10<sup>16</sup> cm<sup>-3</sup> and is lower than 10<sup>22</sup> cm<sup>-3</sup>.
- (previously presented): A semiconductor device in which the p-type semiconductor material according to claim 1, constitutes a hole injecting electrode layer in an amorphous phase or a polycrystalline phase.
- 10. (original): The semiconductor device according to claim 9, wherein the semiconductor device is a light emitting device.
- 11. (previously presented): The p-type semiconductor material according to claim 2, wherein the semiconductor material contains at least one dopant selected from Cl, Br, I, Al, Ga and In as a compensation dopant and a concentration of the compensation dopant is 10<sup>17</sup> to 10<sup>20</sup> cm<sup>3</sup>.
- (previously presented): The p-type semiconductor material according to claim 3,
   wherein the semiconductor material contains at least one dopant selected from Cl, Br, I, Al, Ga

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and In as a compensation dopant and a concentration of the compensation dopant is  $10^{17}$  to  $10^{20}$  cm<sup>-3</sup>

- 13. (previously presented): The p-type semiconductor material according to claim 4, wherein the semiconductor material contains at least one dopant selected from Cl, Br, I, Al, Ga and In as a compensation dopant and a concentration of the compensation dopant is 10<sup>17</sup> to 10<sup>20</sup> cm<sup>3</sup>
- 14. (previously presented): The p-type semiconductor material according to claim 2, wherein the semiconductor material has a light absorption coefficient of  $5 \times 10^5$  cm<sup>-1</sup> or less at 470 nm to 750 nm.
- 15. (previously presented): The p-type semiconductor material according to claim 3, wherein the semiconductor material has a light absorption coefficient of  $5 \times 10^5$  cm<sup>-1</sup> or less at 470 nm to 750 nm.
- 16. (previously presented): The p-type semiconductor material according to claim 4, wherein the semiconductor material has a light absorption coefficient of  $5 \times 10^5 \text{ cm}^{-1}$  or less at 470 nm to 750 nm.
- 17. (previously presented): The p-type semiconductor material according to claim 2, wherein a volume resistivity of the semiconductor material is equal to or higher than  $10^{4}\Omega cm$  and is lower than  $10^{3}\Omega cm$ .
- 18. (previously presented): The p-type semiconductor material according to claim 3, wherein a volume resistivity of the semiconductor material is equal to or higher than  $10^{-4}\Omega cm$  and is lower than  $10^{3}\Omega cm$ .

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- 19. (previously presented): The p-type semiconductor material according to claim 4, wherein a volume resistivity of the semiconductor material is equal to or higher than  $10^{-4}\Omega$ cm and is lower than  $10^{3}\Omega$ cm.
- 20. (previously presented): The p-type semiconductor material according to claim 2, wherein a carrier concentration of the semiconductor material is equal to or higher than 10<sup>16</sup> cm<sup>-3</sup> and is lower than 10<sup>22</sup> cm<sup>-3</sup>.
- 21. (previously presented): The p-type semiconductor material according to claim 3, wherein a carrier concentration of the semiconductor material is equal to or higher than 10<sup>16</sup> cm<sup>-3</sup> and is lower than 10<sup>22</sup> cm<sup>-3</sup>.
- 22. (previously presented): The p-type semiconductor material according to claim 4, wherein a carrier concentration of the semiconductor material is equal to or higher than 10<sup>16</sup> cm<sup>-3</sup> and is lower than 10<sup>22</sup> cm<sup>-3</sup>.
- 23. (previously presented): A semiconductor device in which the p-type semiconductor material according to claim 2, constitutes a hole injecting electrode layer in an amorphous phase or a polycrystalline phase.
- 24. (previously presented): A semiconductor device in which the p-type semiconductor material according to claim 3, constitutes a hole injecting electrode layer in an amorphous phase or a polycrystalline phase.
- 25. (previously presented): A semiconductor device in which the p-type semiconductor material according to claim 4, constitutes a hole injecting electrode layer in an amorphous phase or a polycrystalline phase.

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 (previously presented): The semiconductor device according to claim 23, wherein the semiconductor device is a light emitting device.

- 27. (previously presented): The semiconductor device according to claim 24, wherein the semiconductor device is a light emitting device.
- 28. (previously presented): The semiconductor device according to claim 25, wherein the semiconductor device is a light emitting device.